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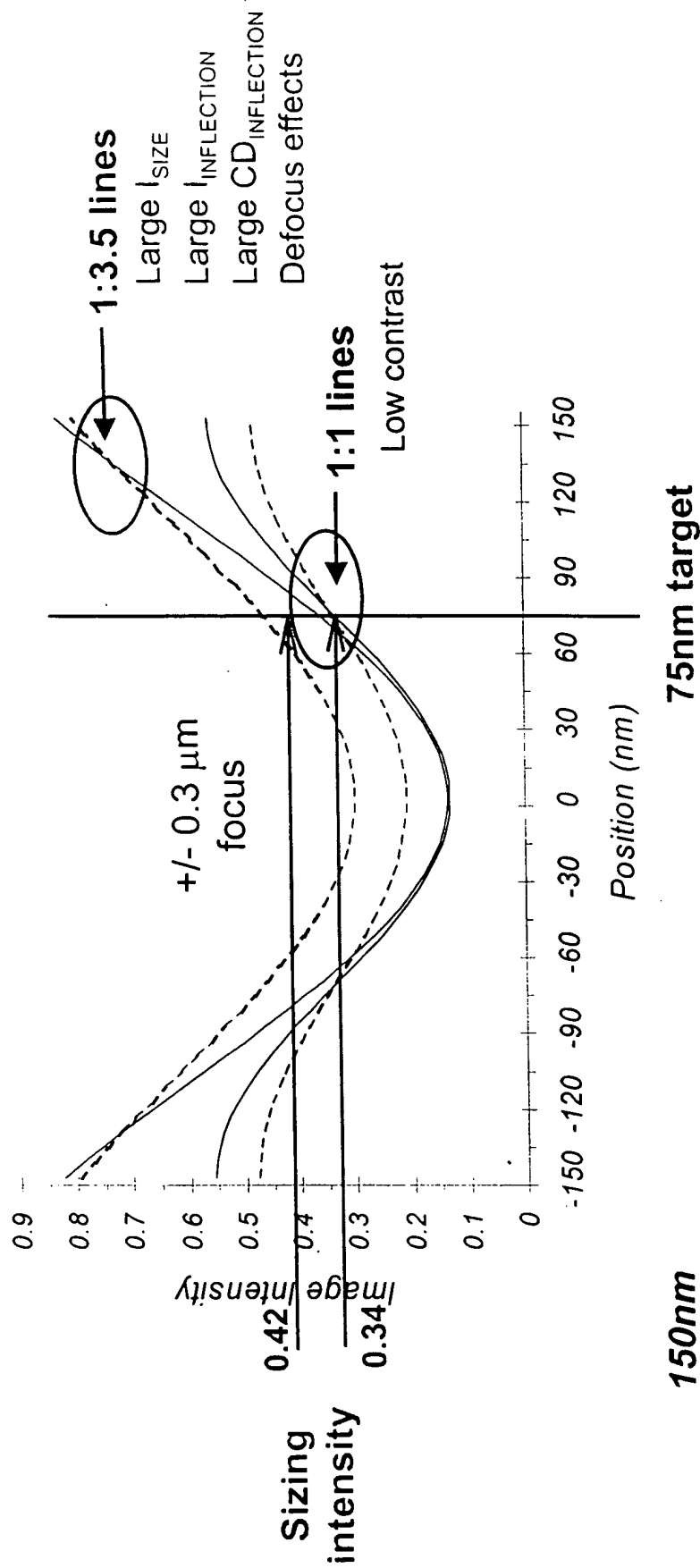
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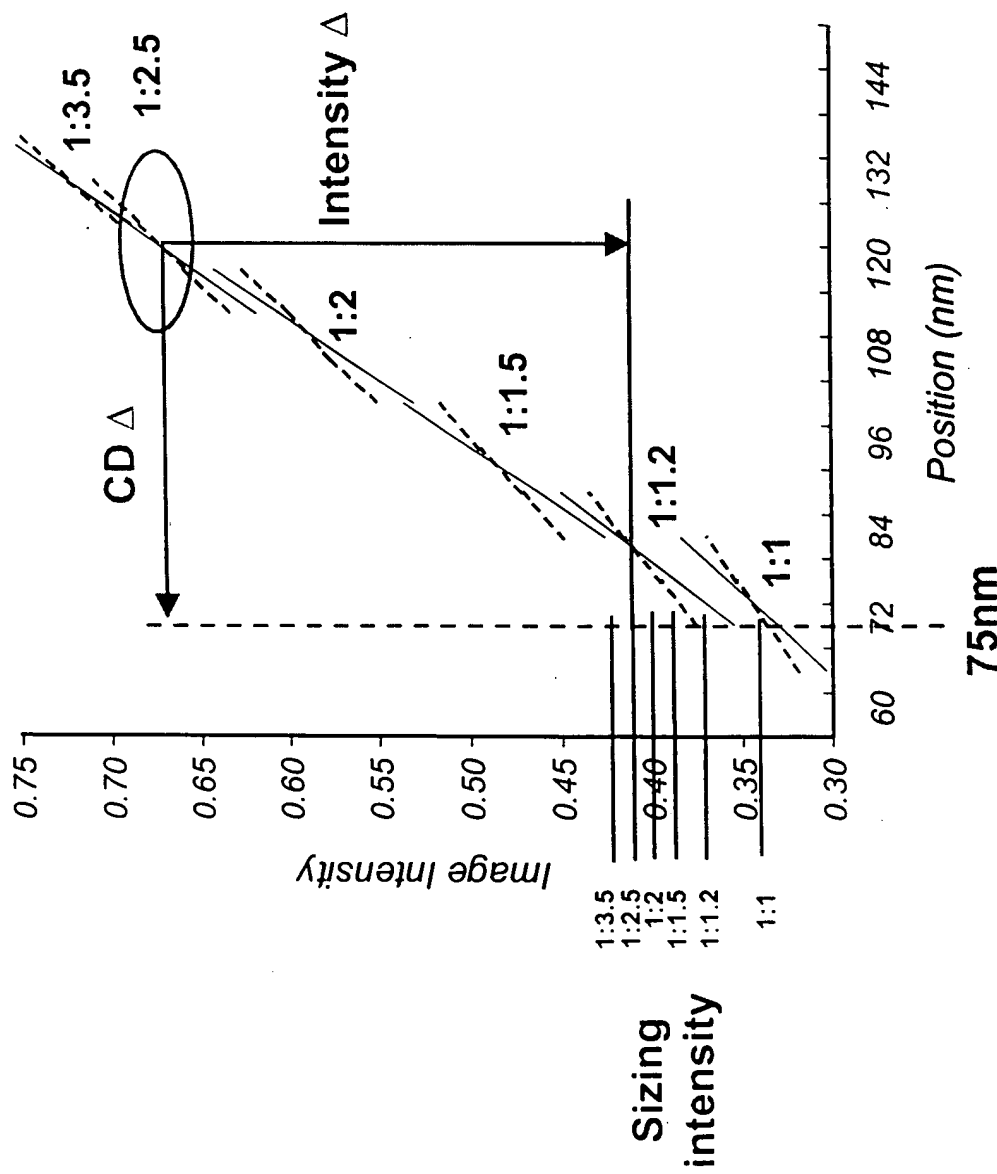
Figure 1. Introduction to Imaging Problems

Aerial images for two cases



248nm, 0.70NA, 0.85 σ

Figure 2. Key image CD/intensity locations
150nm geometry



GOALS

- Increase image contrast and slope
- Drive intensity to common inflection
- Move inflection CD toward sizing CD
- Decrease across pitch differences

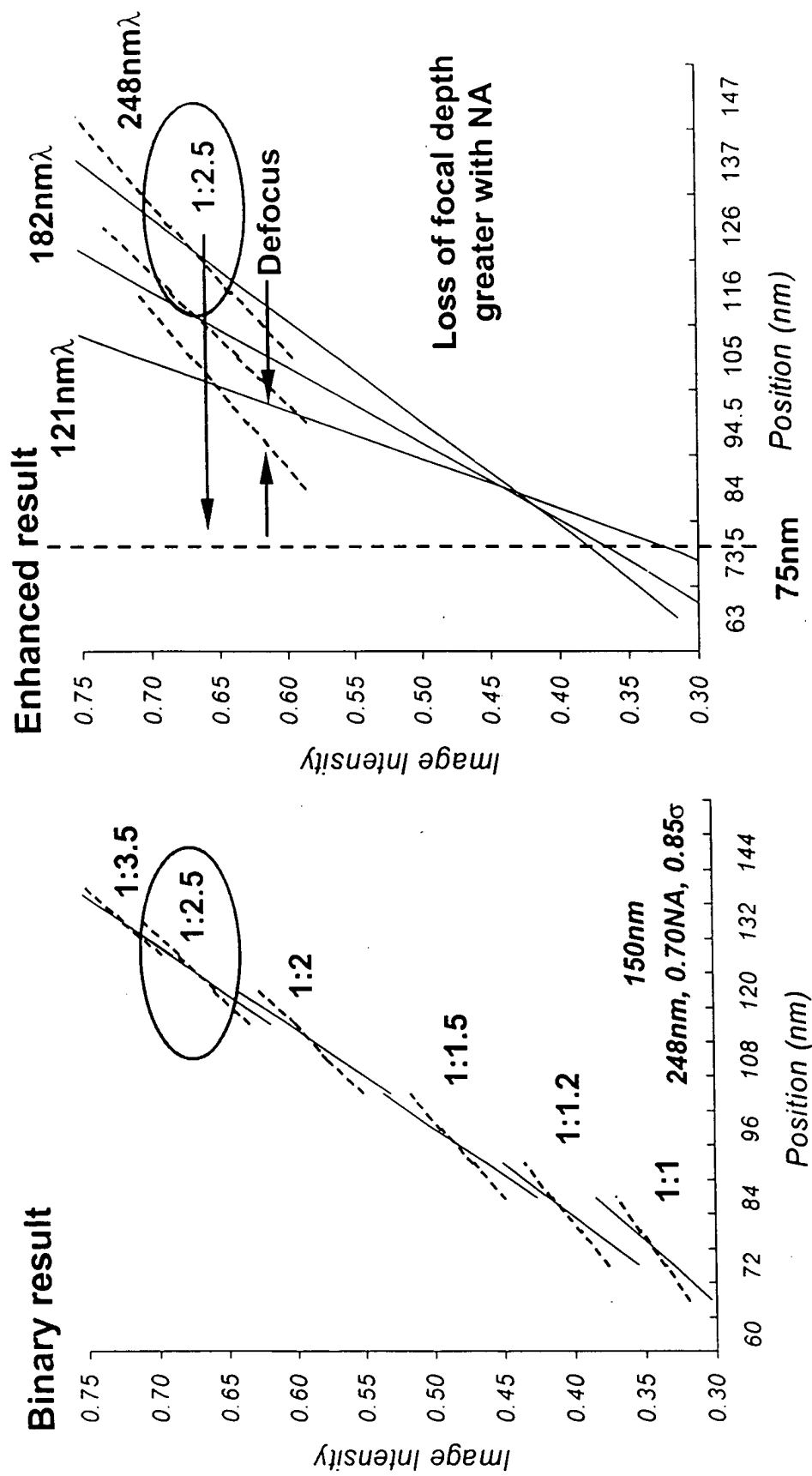
METHODS

- Illumination
- Object (mask)
- Frequency filtering





**Figure 3. Improvements with wavelength
Shift of CD with additional orders**



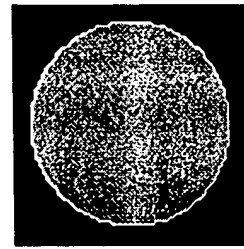
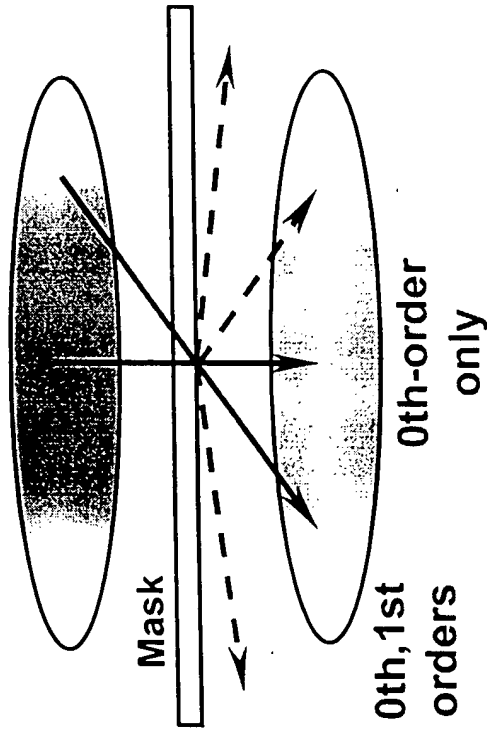
Can Image Modifications lead to improvement?

Figure 4. Image contribution for small pitch
One and two order imaging

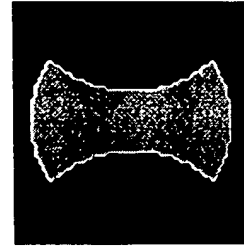
Illumination can be broken down into contributing parts

There is no three-order interference with

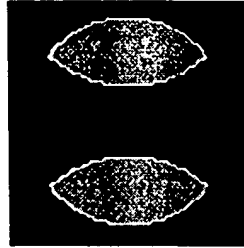
$$p < \lambda/(\sigma+1)NA$$



=



+



150nm 1:1
248nm/0.7NA/
0.85 σ

Full Illuminator

Zero only
(one-order)
contribution

Zero and 1st
(two-order)
contribution





Figure 5. Illumination of various pitch values

Illumination has separate and *predictable* components

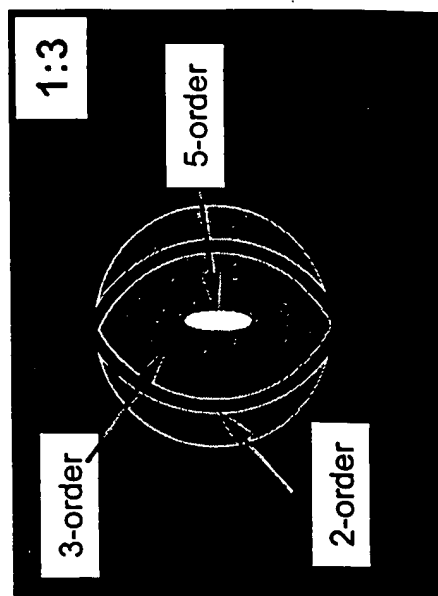
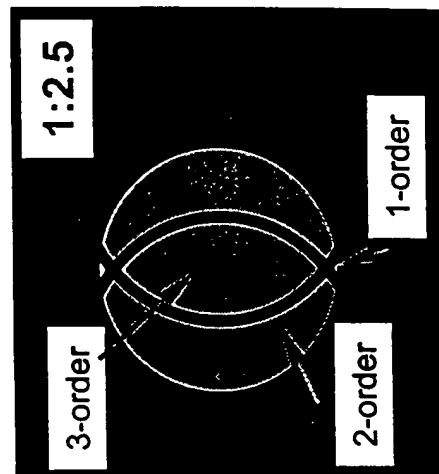
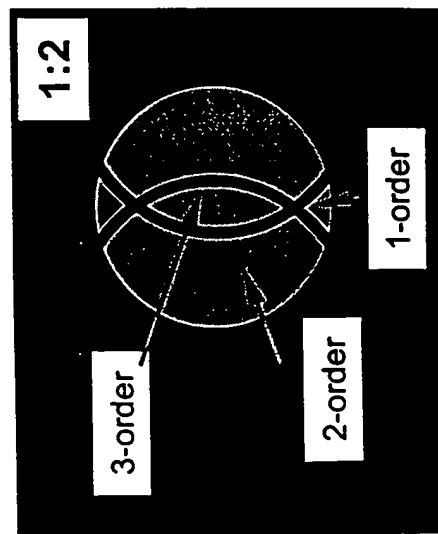
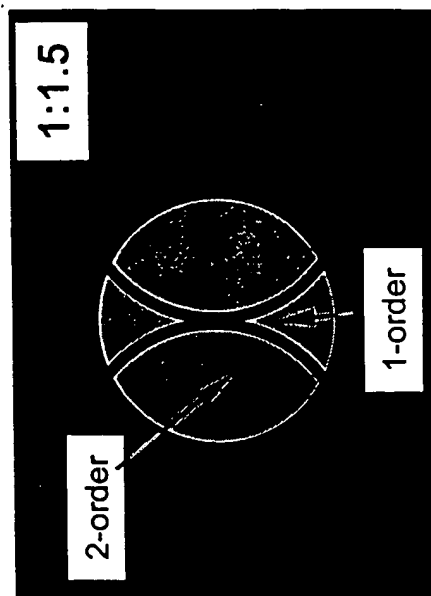
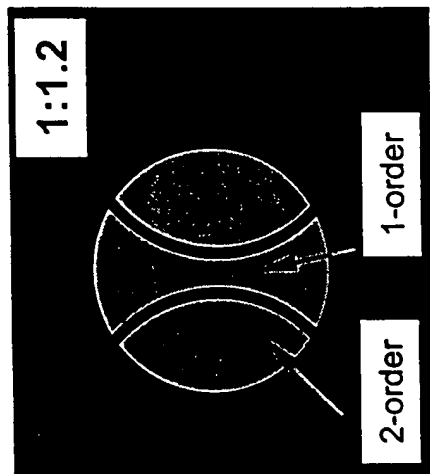
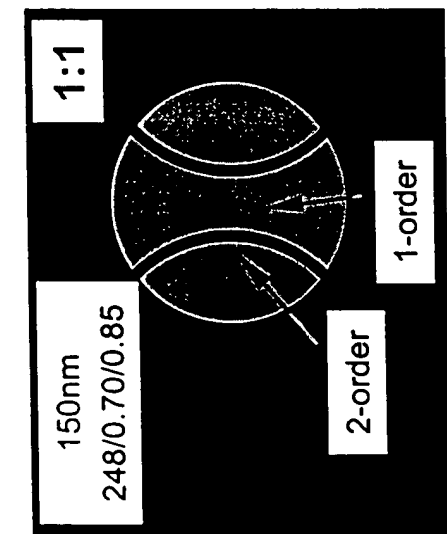




Figure 6. One and two order imaging
150nm 1:1

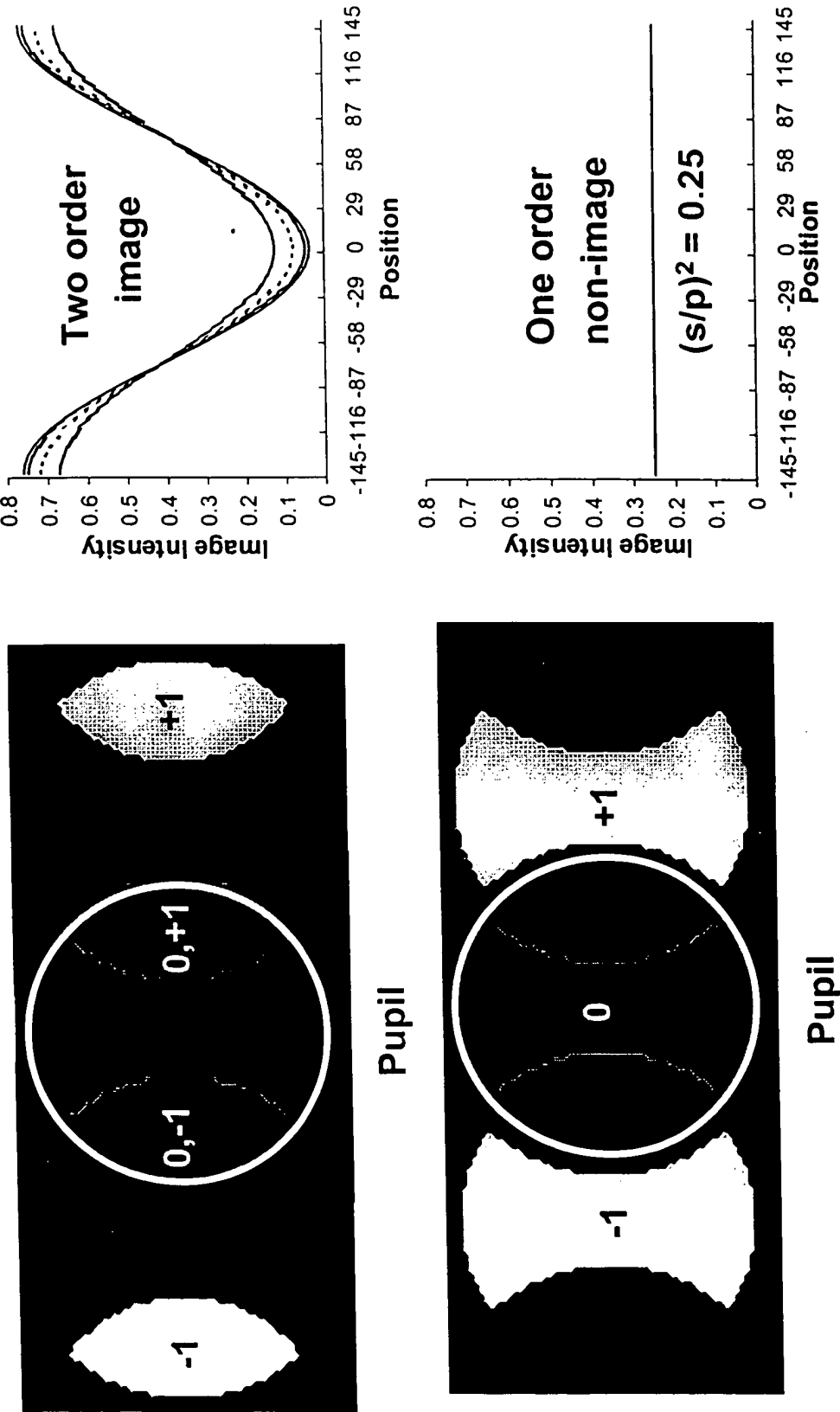
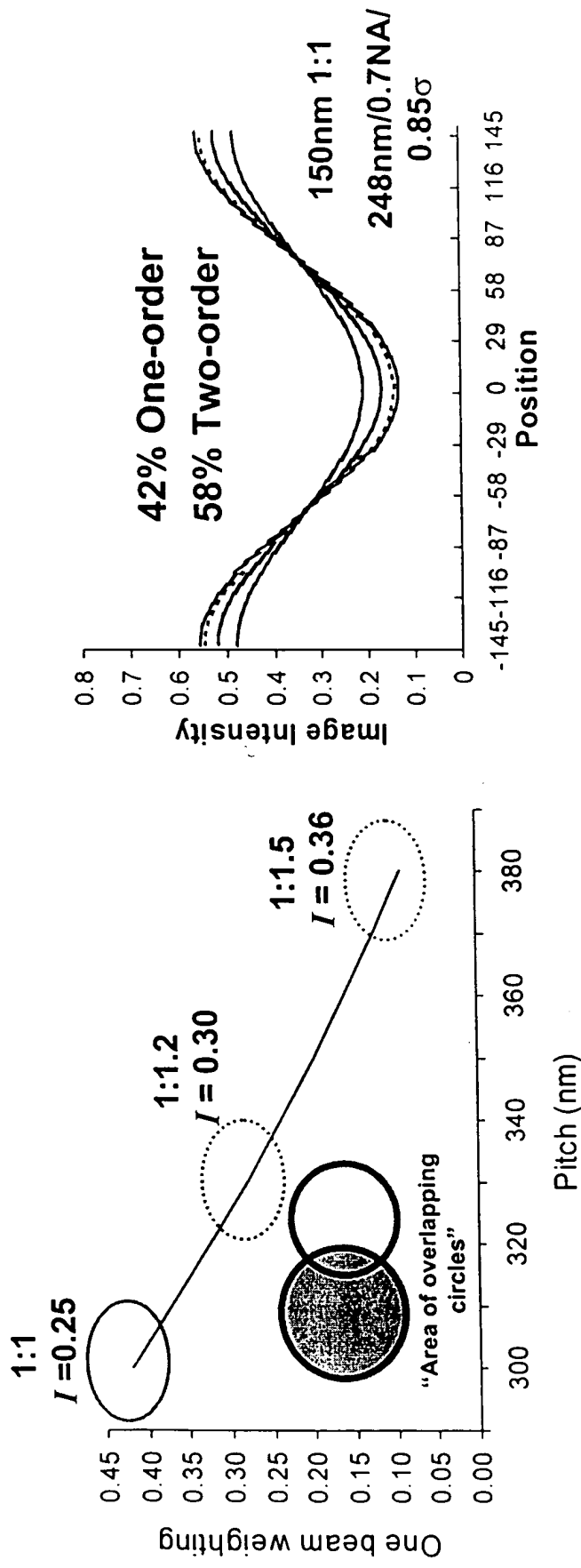


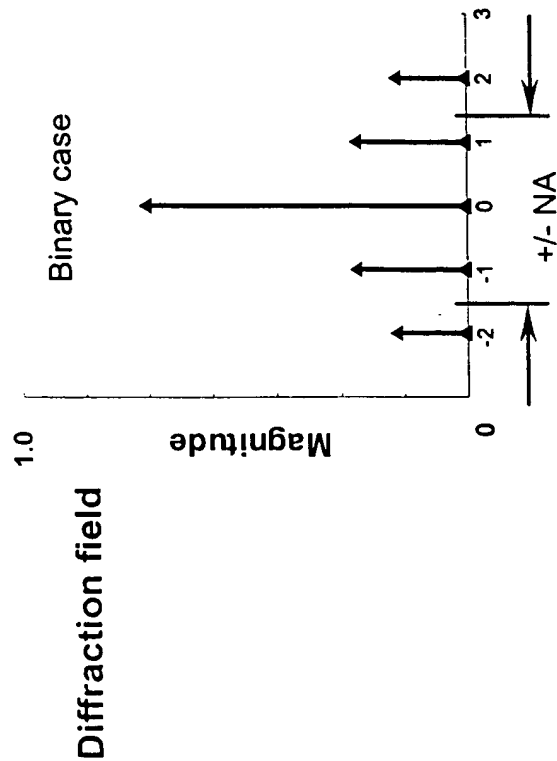
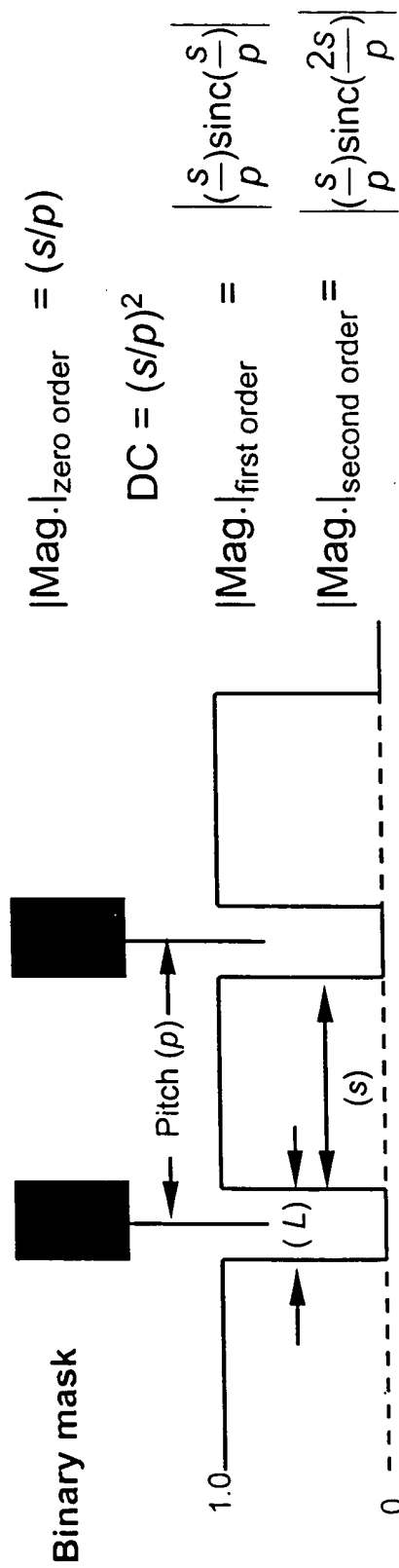


Figure 7. Image contribution - weighting of components



- 42% of the 1:1 image is one order "non-image" intensity (I) of 0.25
- Three-order imaging begins at $>1:1.55$ (one order diminishes)
- Illumination should be tailored to reduce non-image contribution
- *Predictable* from frequency domain

Figure 8. Mask E-field and diffraction order magnitude

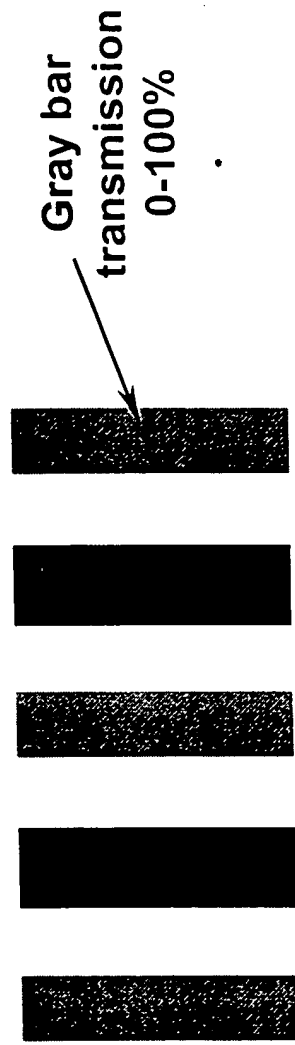


How can the mask E-field be modified-

- PSM
- Field modification
- More general solutions



**Figure 9. Modification of Mask E-field
The use of Gray Bars**



1:2.5 lines
(150nm / 375nm)

0.33 space-width Gray Bars (125nm)

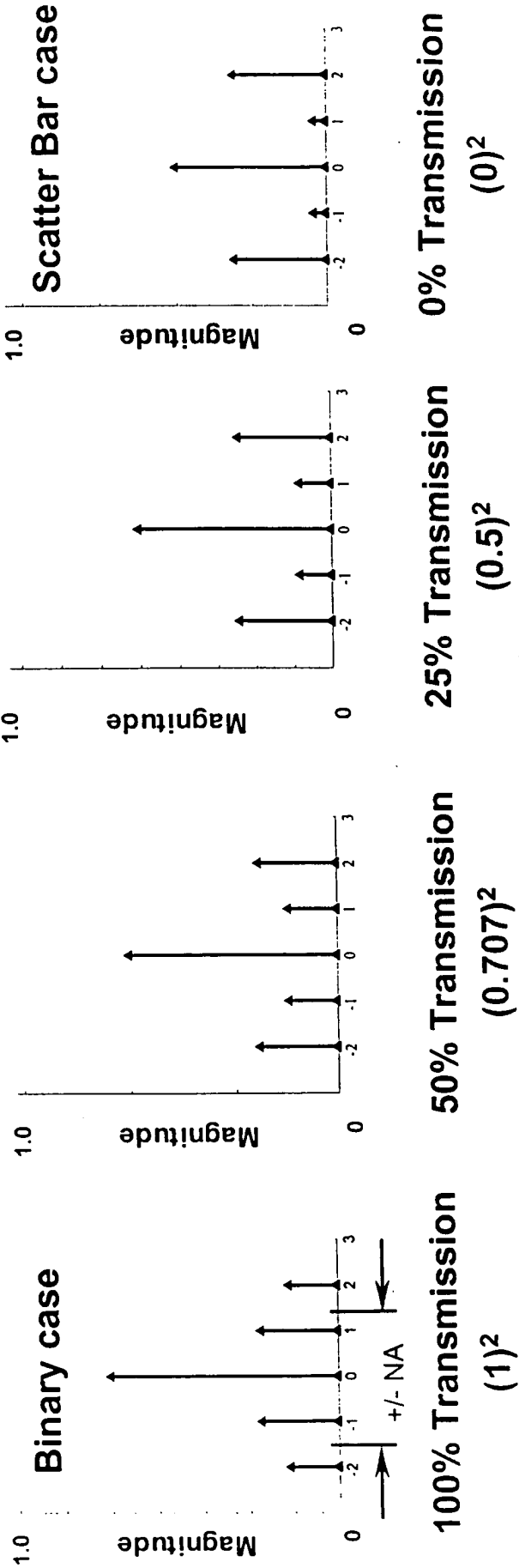


Figure 10. Mask E-field and diffraction energy with Gray Bars

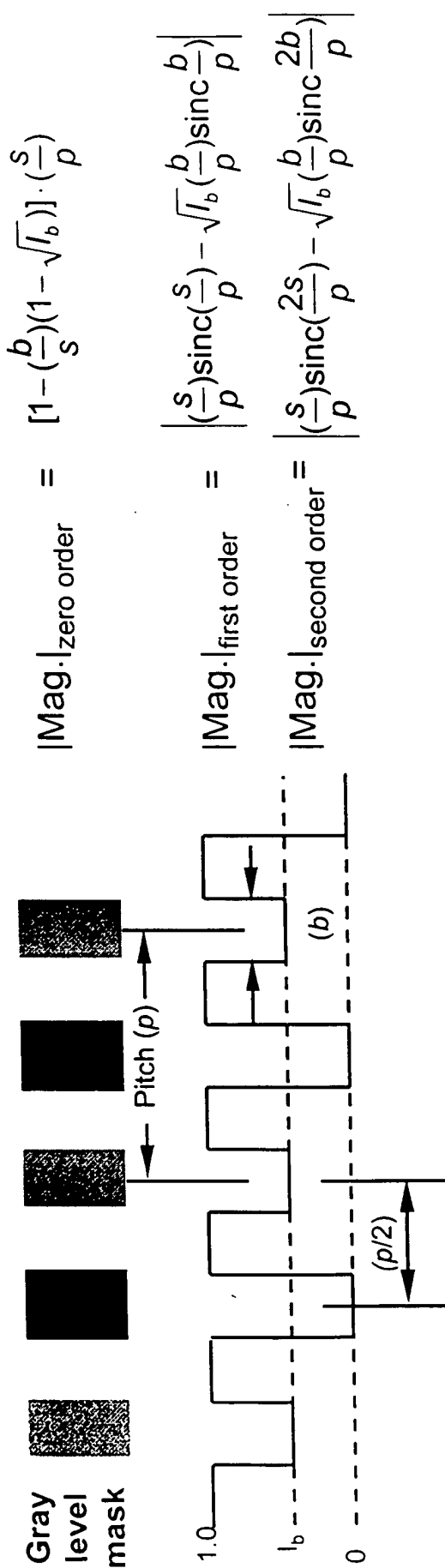




Figure 11. Diffraction energy control using Gray Bars

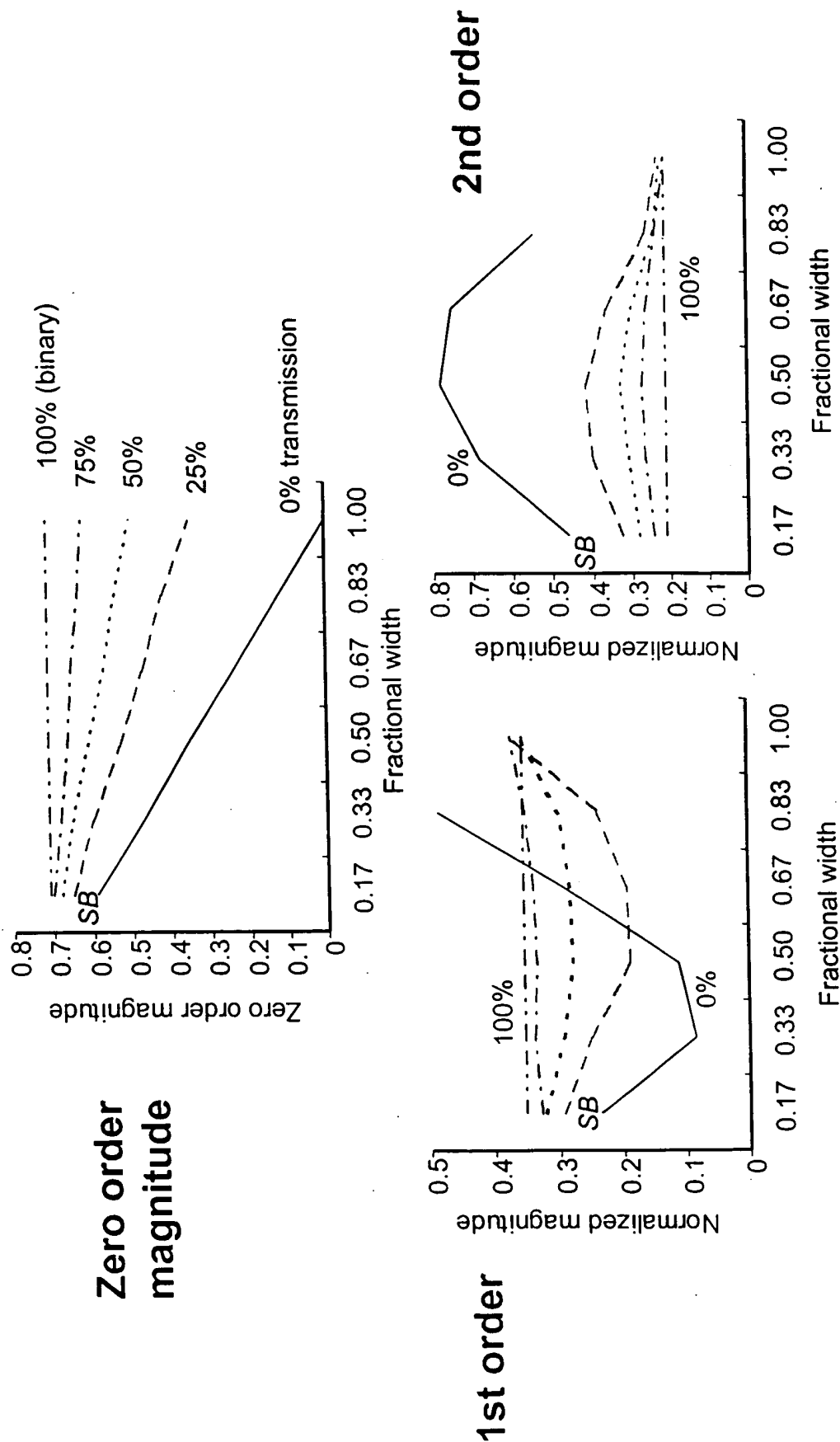
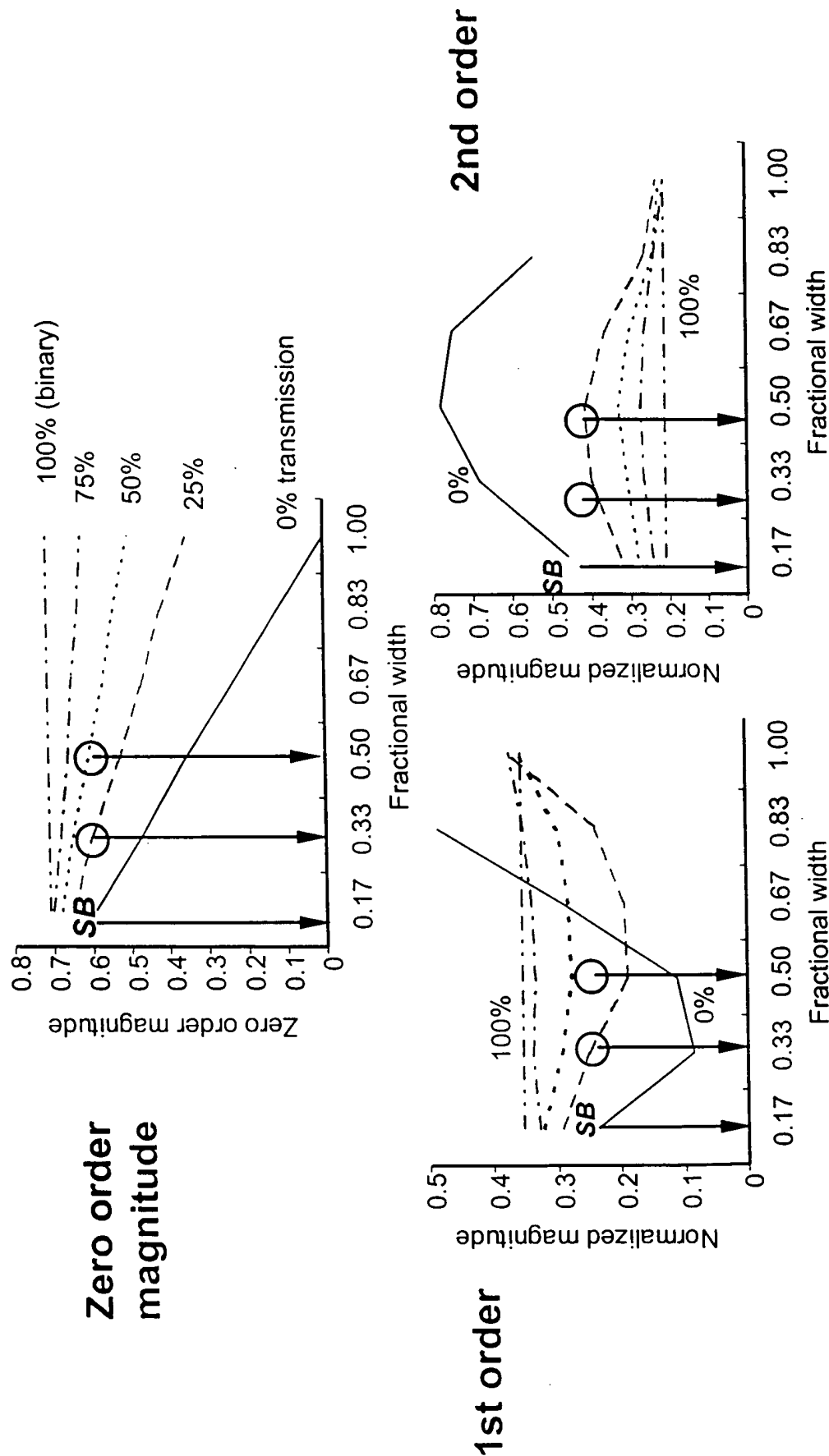


Figure 12. Equivalent solutions for Gray Bars and SBs



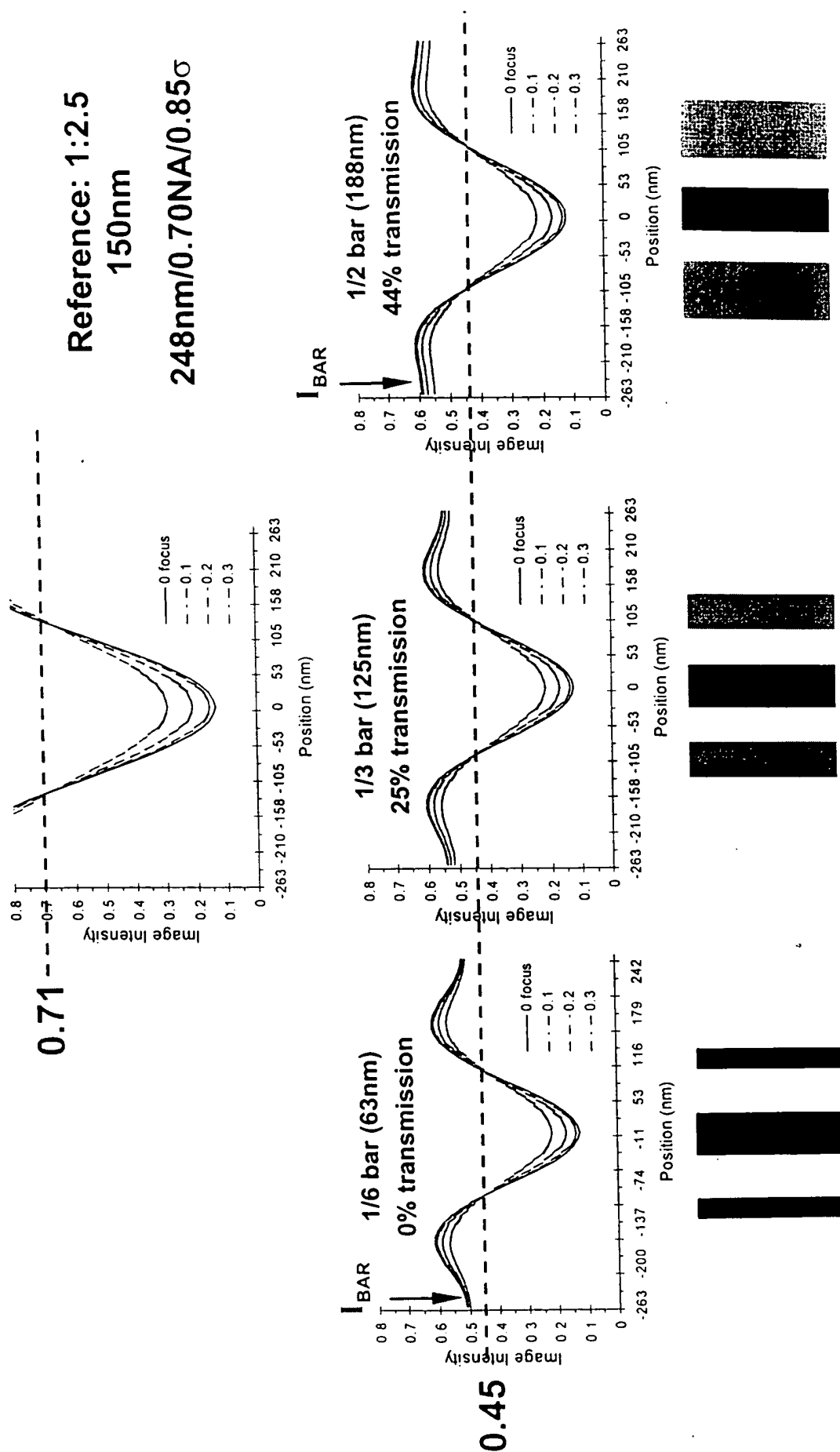
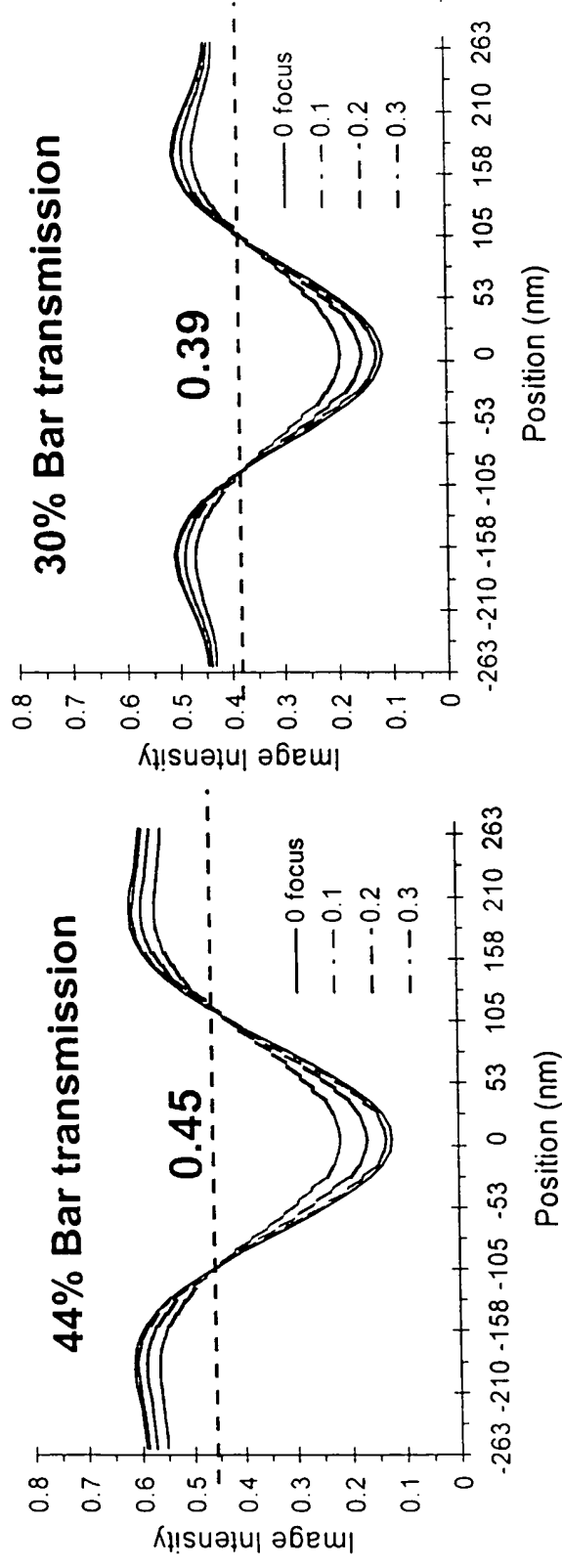


Figure 14. Gray Bar tuning

$$(b/s) = 1/2$$

188nm gray bar



- Printability of the gray bar is low because of the dampened 2nd order influence
- Gray bar sizing is practical $0.10s < \text{bar} < 0.7s$ and $\text{bar} = 0s$ & $1s$ (mask dependant)
- Adverse OAI influence with gray bar is reduced over dark bar
- 25-50% gray bar transmission is a good general solution



Figure 15. Image CD / intensity results with Gray Bars

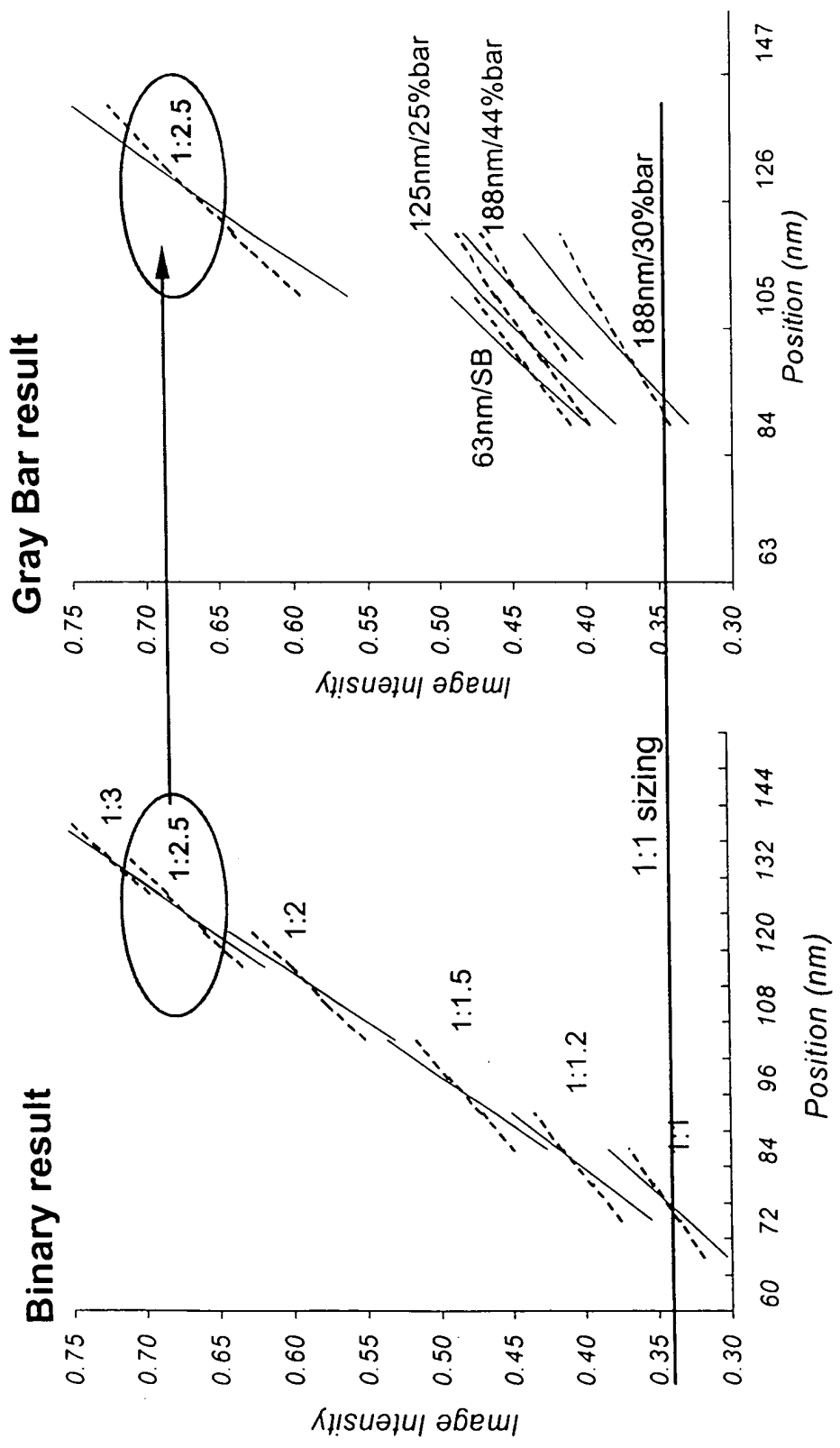
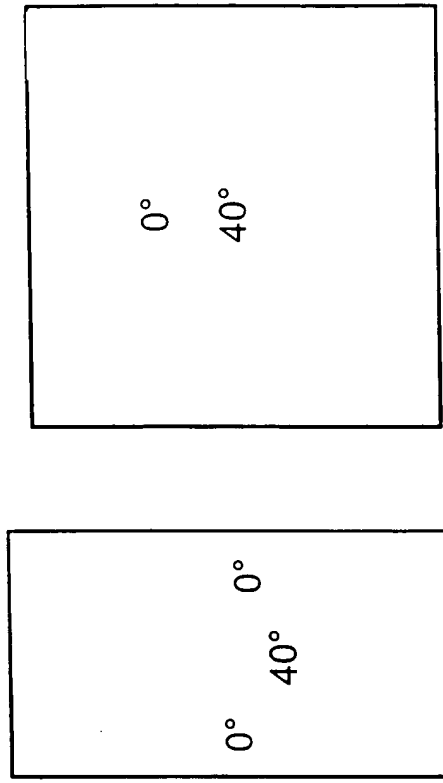
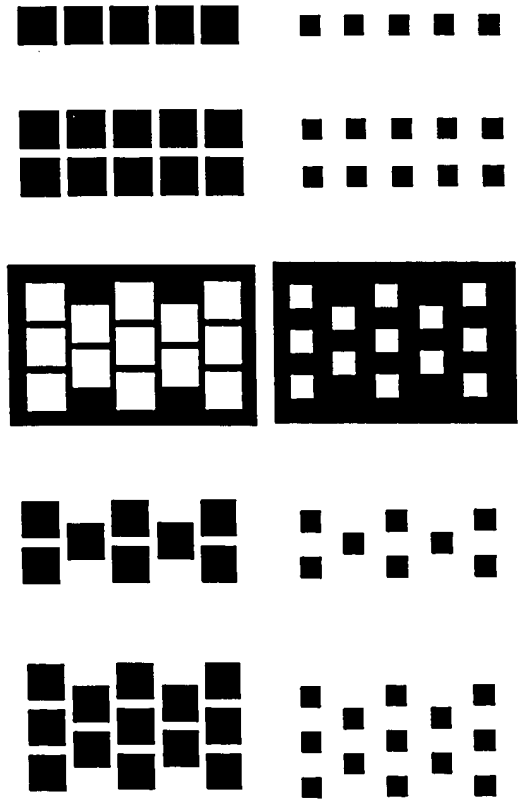


Figure 16. Gray Bar methods
 Chrome or sub- π phase attenuation



Odd-bars give focus asymmetry
 Even-bars give image asymmetry

Sub- π checkerboards avoid asymmetry



Island arrays

Pitch (nm)	Transmission
80	21%
100	45%
120	62%
140	74%

Phase (deg)	Transmission
40	12%
60	25%
80	42%
100	60%



Figure 17. Gray Bar methods
Multiple level mask

- Films deposited for 50% transmission**
- Composite Si_xN_y at 88% Si_3N_4 with 12% Si
 - Sputter deposited from Si at 1000W in Ar/N2
 - Etch selectivity to CrON via SF_6 -chemistry
 - Sub-50% transmission via lower Si content

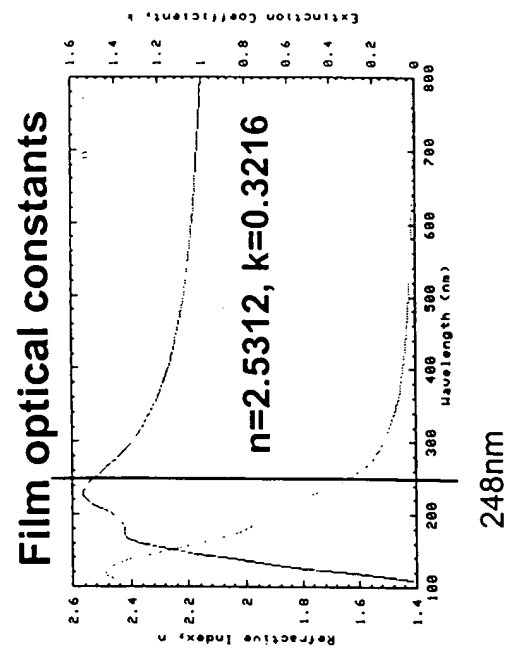
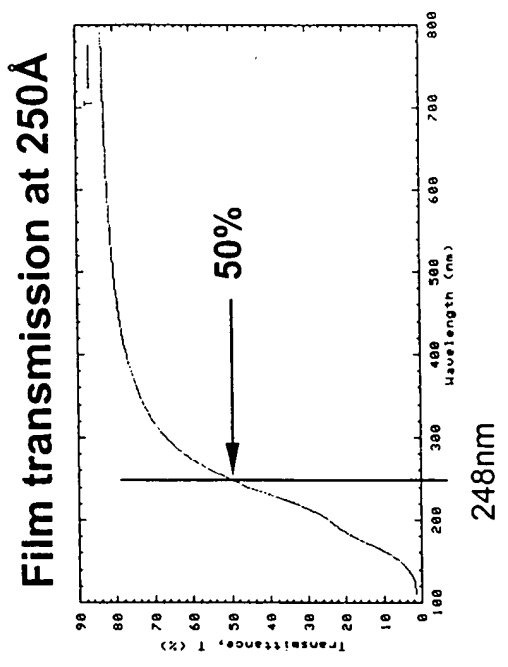
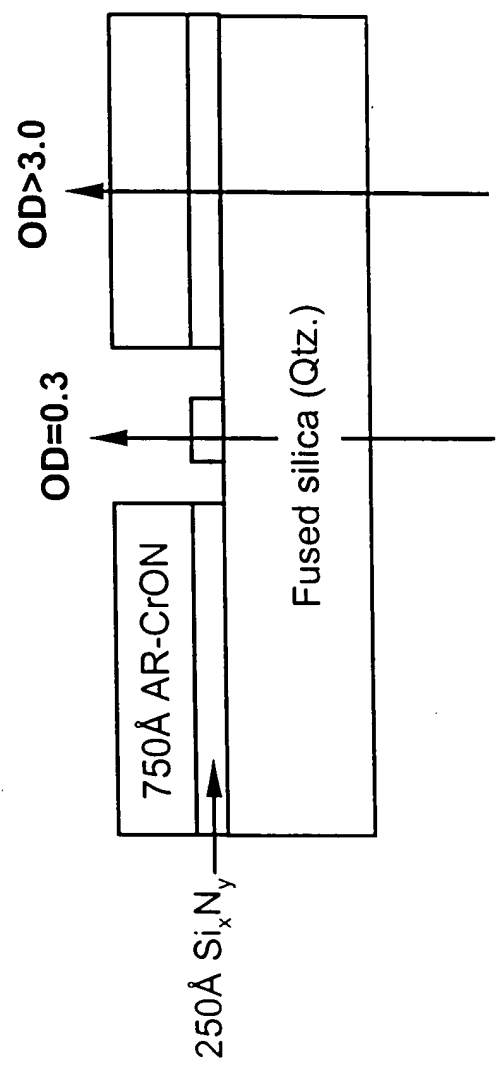


Figure 18. The problem with "gray spacing"

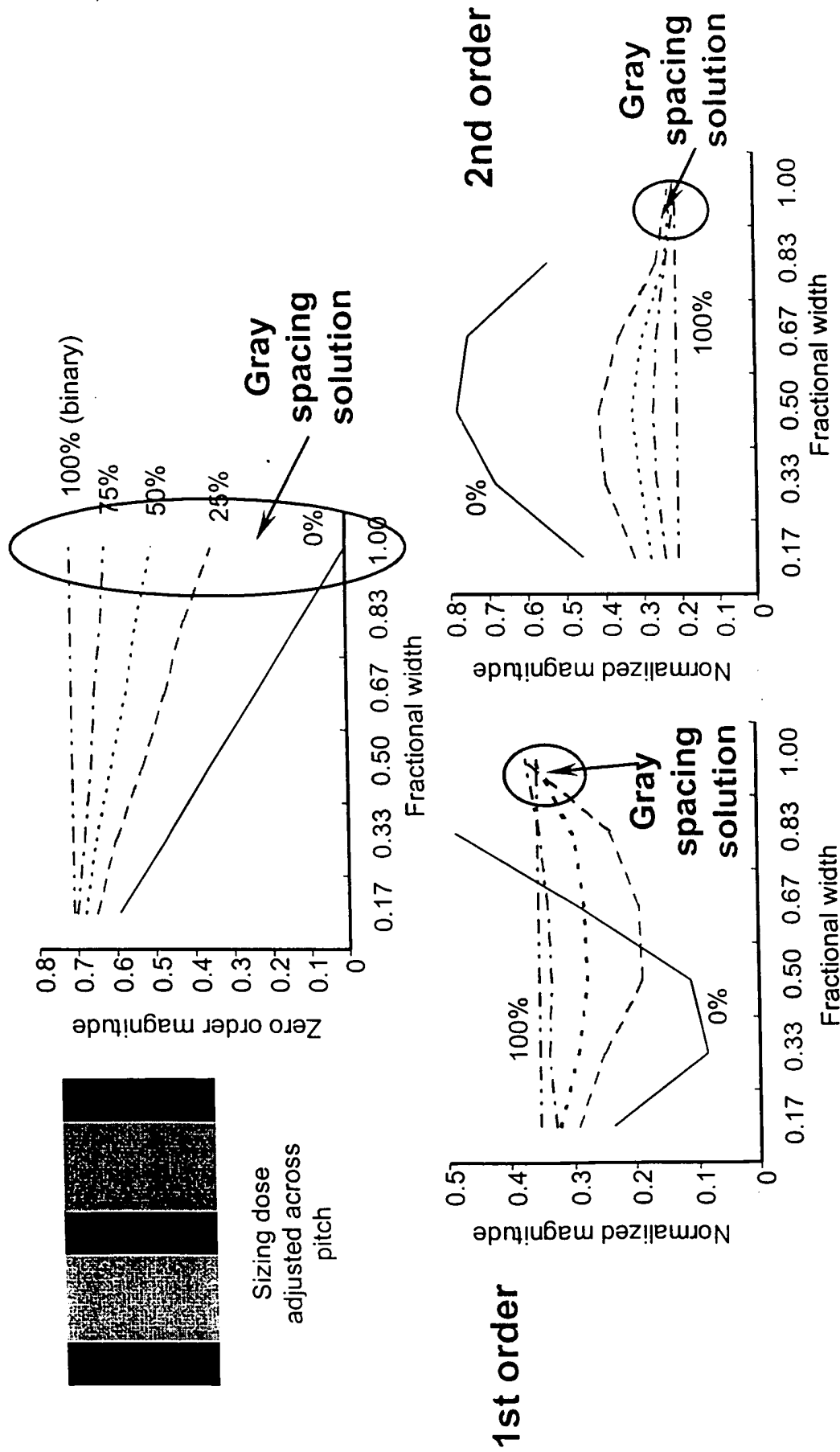
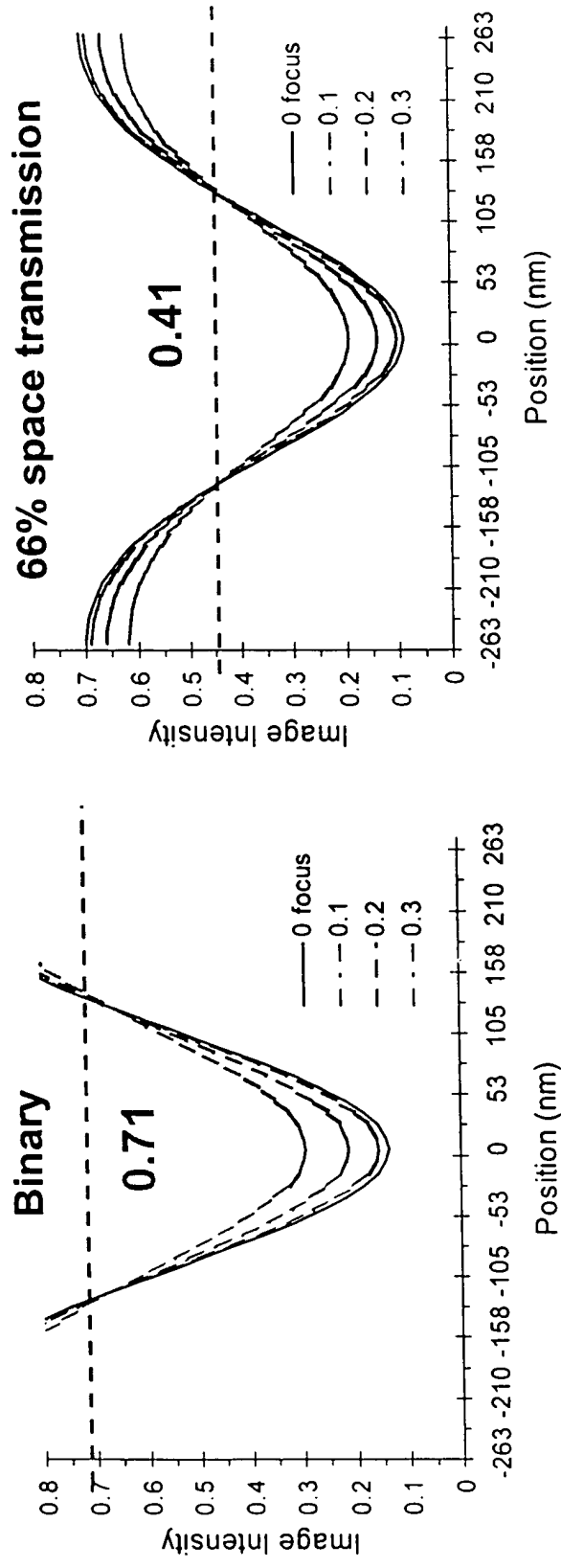
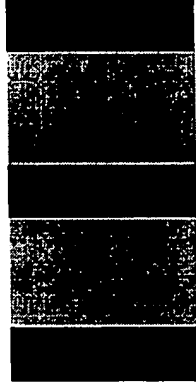


Figure 19. Gray spacing solution
Reduction in Intensity Δ



1. Uniform decrease in all orders - loss of modulation
2. Does not reduce isofocal CD to sizing delta
3. Limited solution

**Figure 20. Impact of gray scaling
Reduction only in Intensity to sizing Δ**

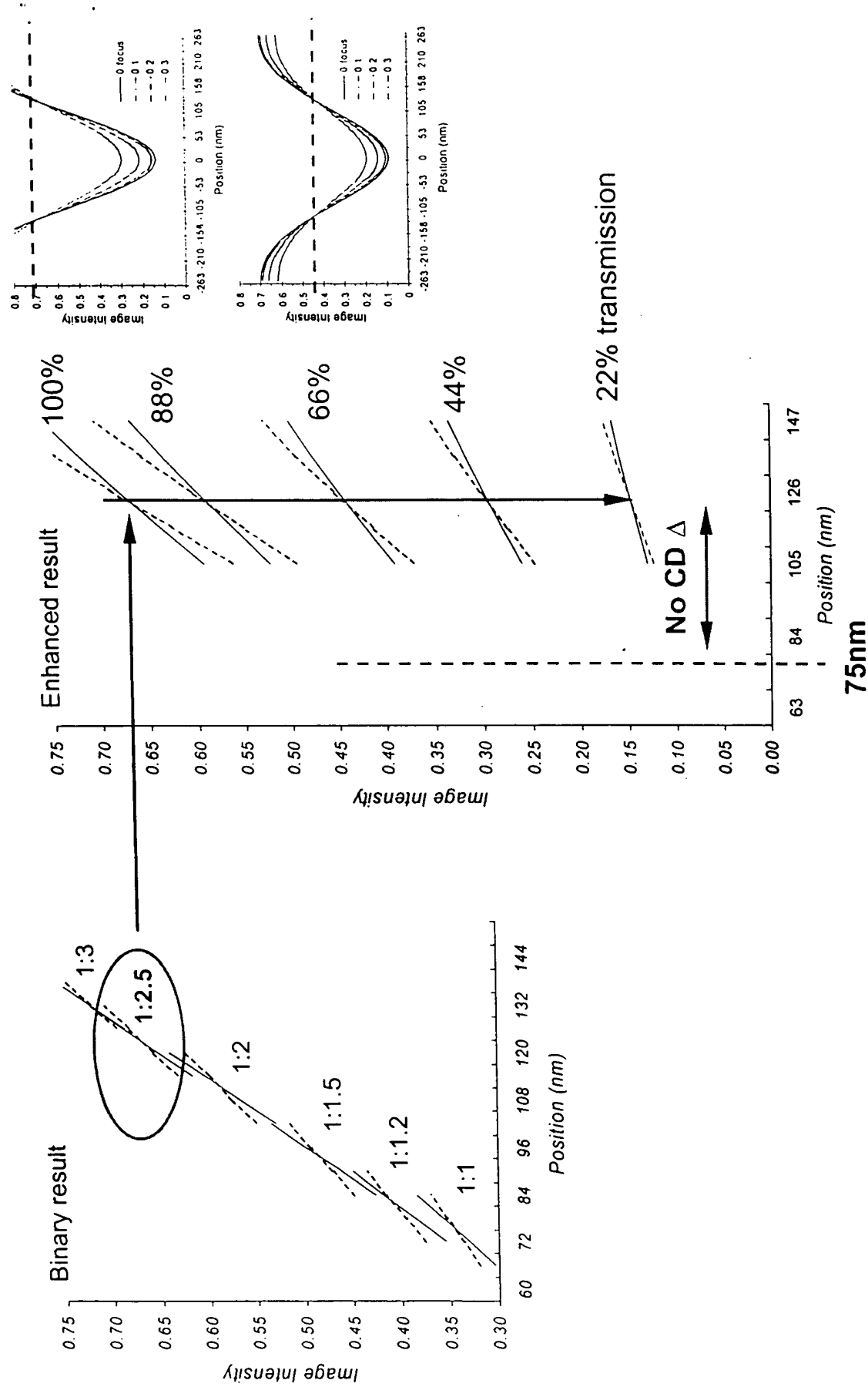


Figure 21. Illumination control of diffraction energy

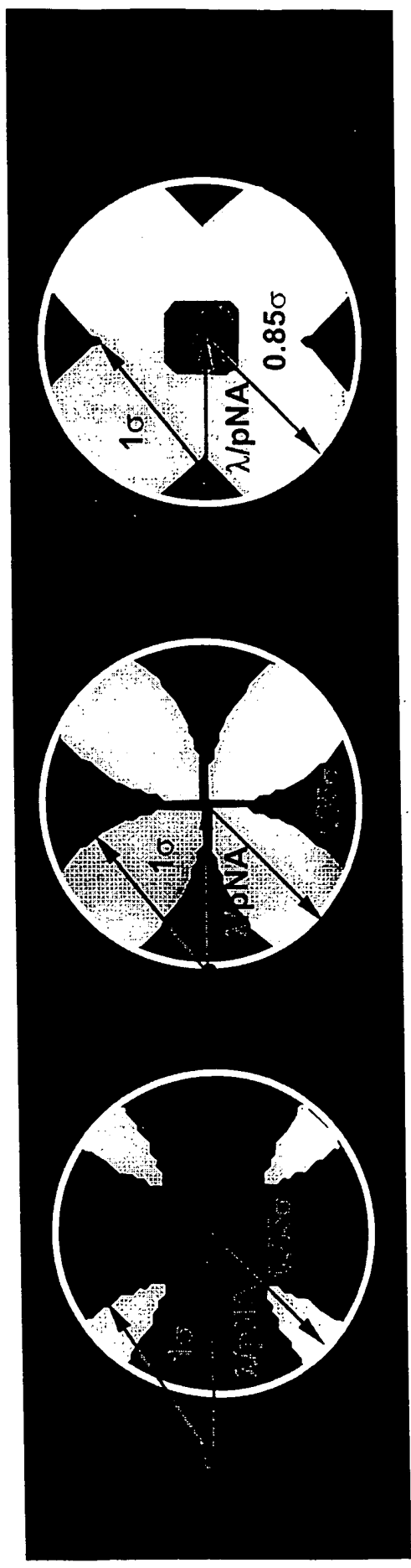
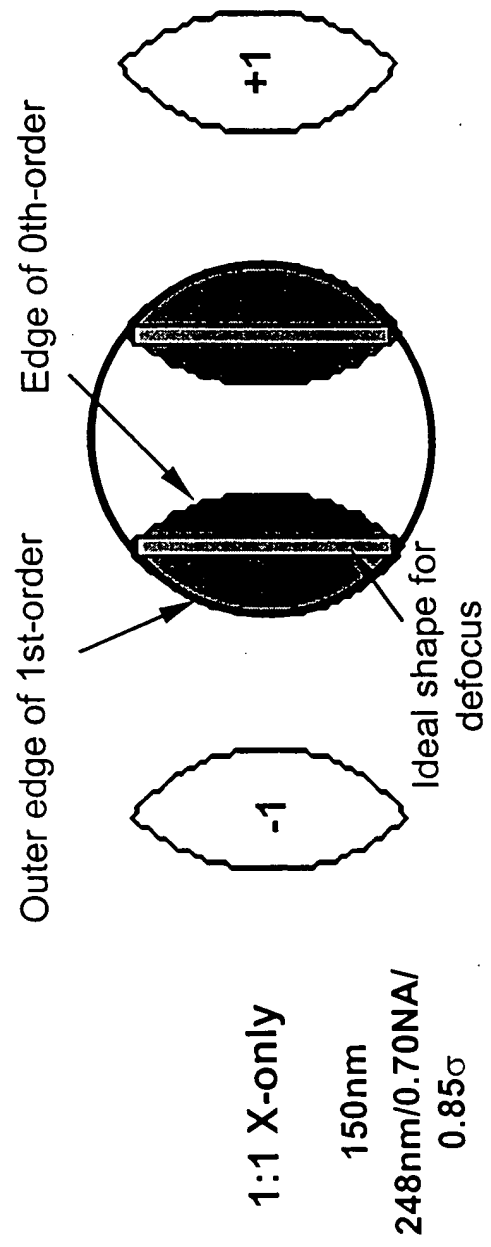
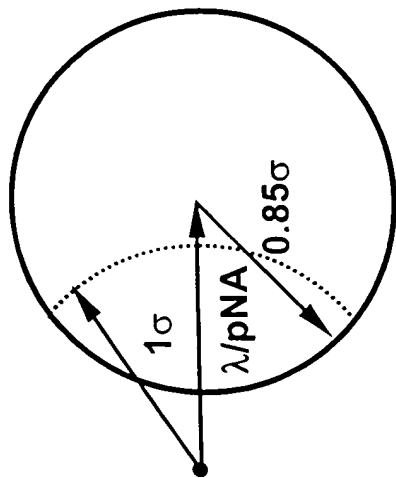
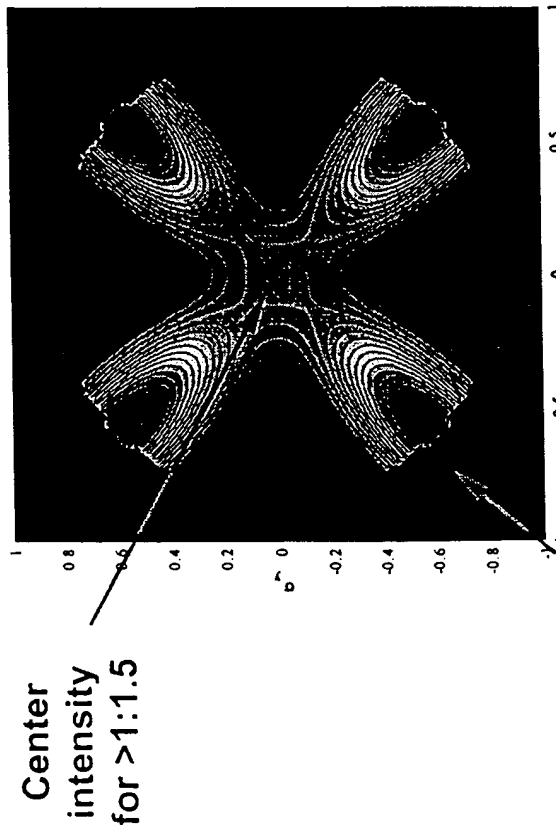


Figure 22. Custom source for dense /semi-dense features



Method for layout

Parameters to define: pitch, NA, and σ
 Best source for each pitch is designed
 Weighting is chosen and sources are combined



Center
intensity
for >1:1.5

Corner illumination at
 0.85 σ for 1:1 to 1:1.5



Figure 23. Image results with the custom source

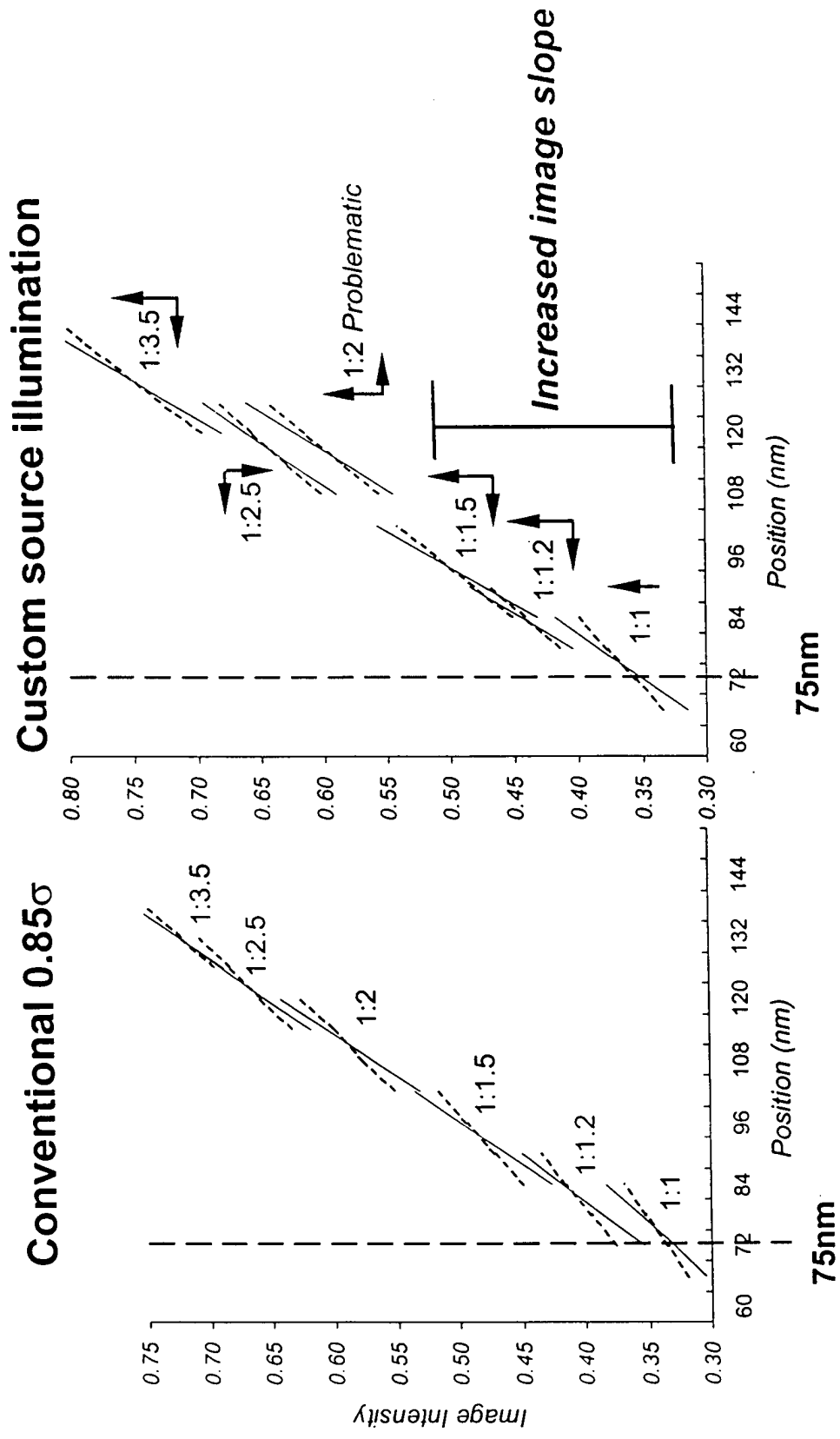


Figure 24. Illumination combined with Gray Bars
150nm 1:1 to 1:3.5

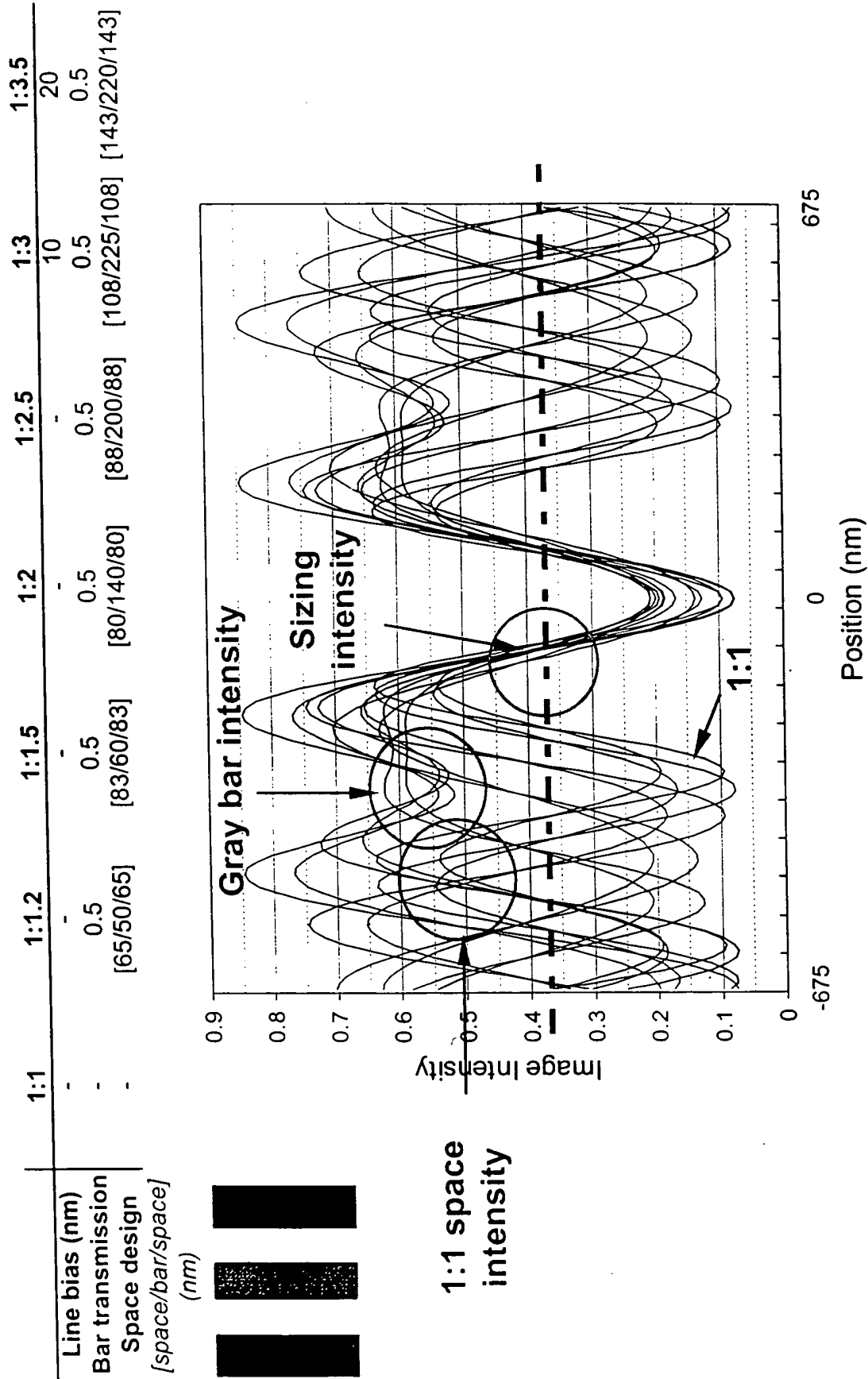




Figure 25. Solving for CD / Intensity inflection

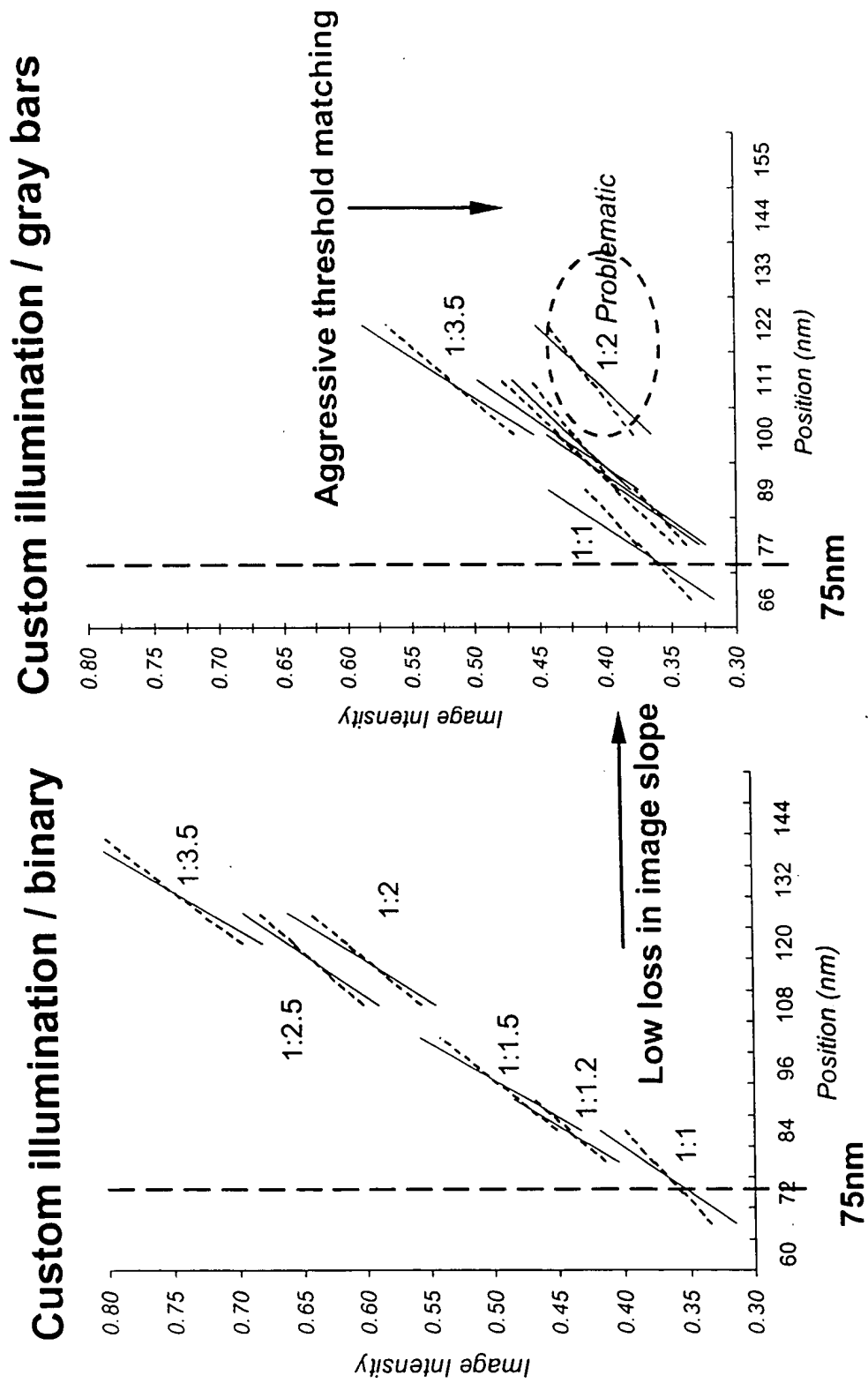
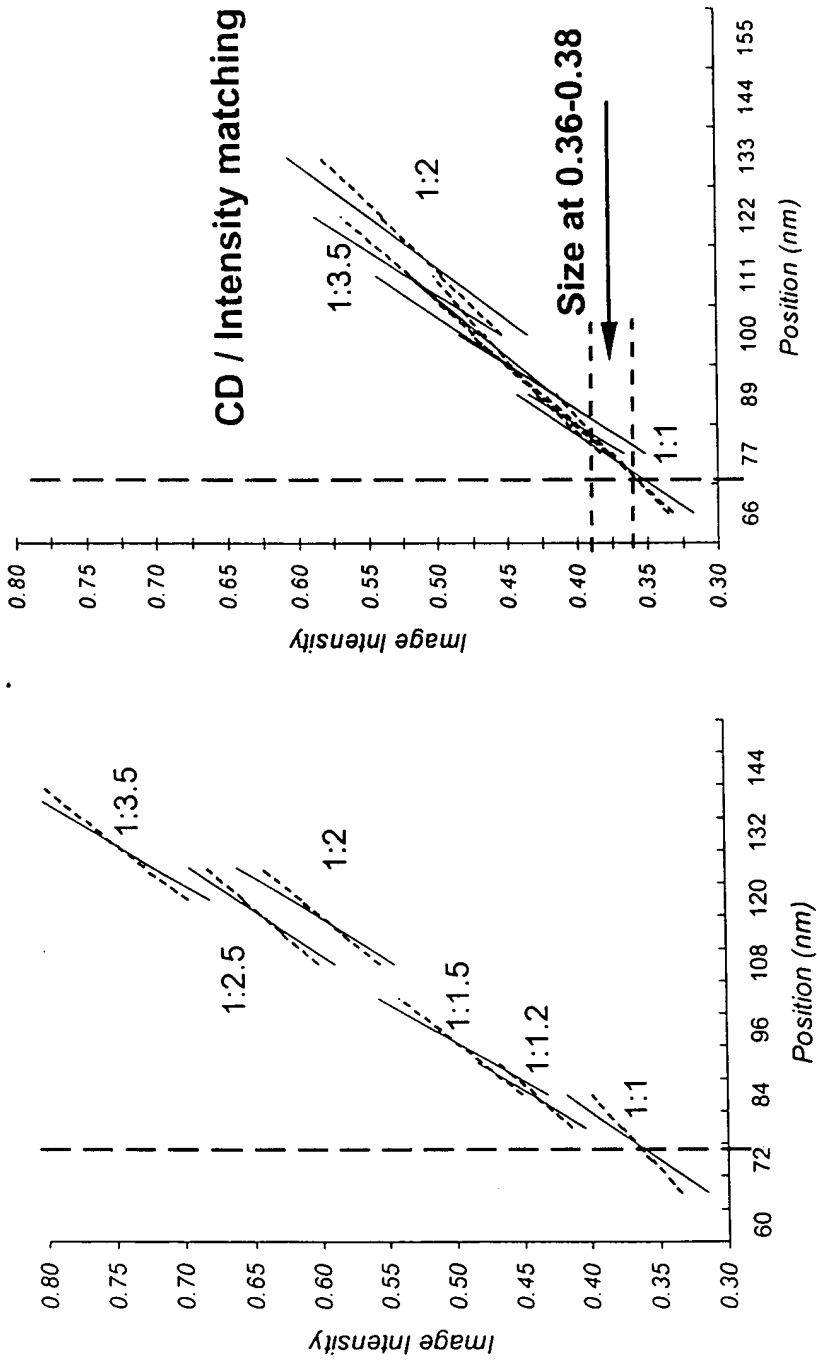




Figure 26. Solving for CD matching

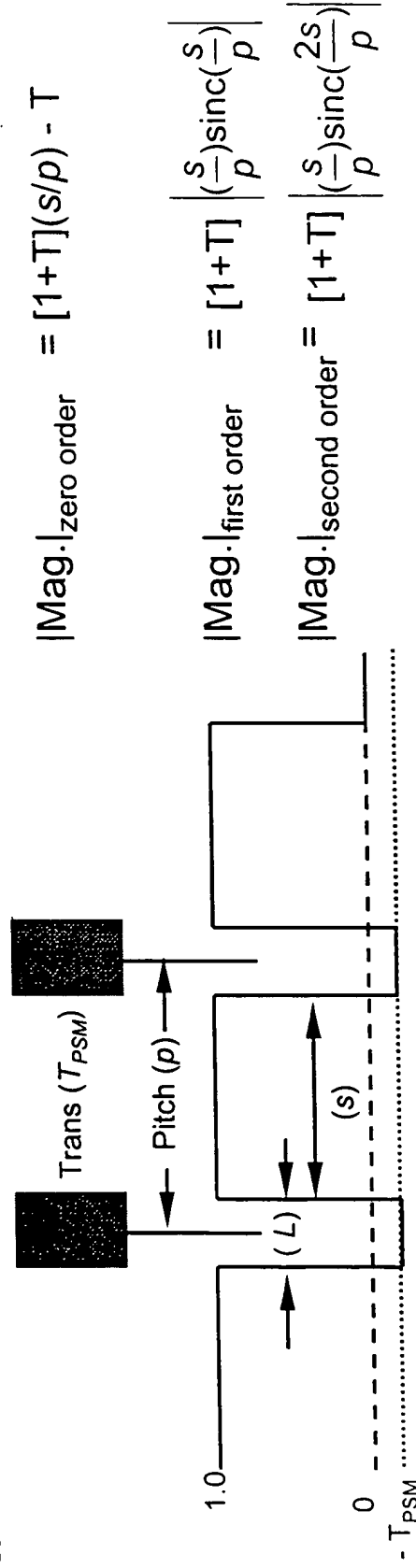
Custom illumination / binary Custom illumination / gray bars



	1:1	1:1.2	1:1.5	1:2	1:2.5	1:3	1:3.5
Line bias (nm)	-	-	-	-	-	10	20
Bar transmission	-	0.5 dots	0.5 dots	0.5	0.5	0.5	0.5
Space design [space/bar/space] (nm)	-	[65/50/65]	[75/75/75]	[120/60/120]	[113/150/113]	[120/200/120]	[143/220/143]

Figure 27. Mask E-field and diffraction energy for AttPSM

AttPSM mask



Pupil filtering

Pupil filtering is a function of illumination and NA

$$\begin{aligned}
 |\text{Mag.}|_{\text{zero order}} &= F_0 (s/p) \\
 |\text{Mag.}|_{\text{first order}} &= F_1 \left| \left(\frac{s}{p} \right) \text{sinc} \left(\frac{s}{p} \right) \right| \\
 |\text{Mag.}|_{\text{second order}} &= F_2 \left| \left(\frac{s}{p} \right) \text{sinc} \left(\frac{2s}{p} \right) \right|
 \end{aligned}$$

Figure 28. Fast ImageSolver

